Sequence Etching and Patterning

with an Ultra-short Pulse Laser

Possible to suppress the removal depth to the order of several hundred Feature1

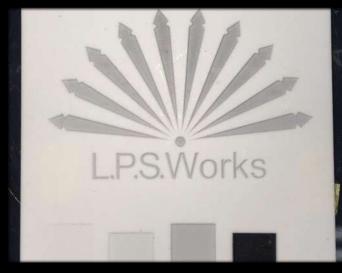
nanometers to several microns

Feature2 Process various materials (e.g., metals, resins, glass and ceramics)

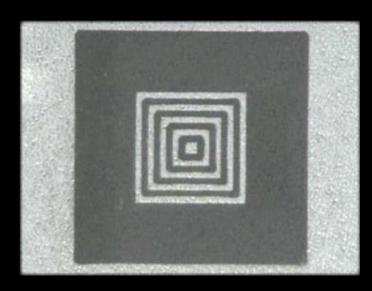
Possible to remove only the surface layer film without damaging Feature3

the base material as far as possible

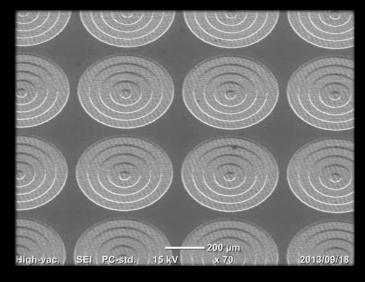
Processing Examples



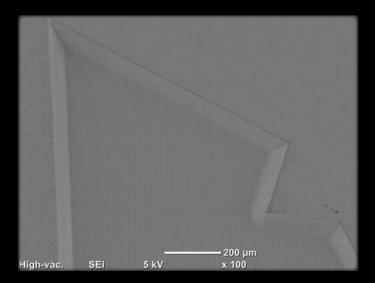
Alumina Ceramic Spot-Facing Processing Depth: 340 μ m / Plate thickness: 380 μ m



Aluminum Film Patterning on PET Film material: Al Plate thickness: 500 Å L/S: 40 μ m / 40 μ m



Sequence Etching on Aluminum Diameter: 50, 150, 250, 350 and 450 μ m respectively Depth: 5 μ m for each stage and 25 μ m overall



Sequence Etching on Zirconia Depth: 160 μ m



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